## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Hiroaki Niimi

Art Unit 2823

Serial No. 09/885,744

Examiner Nguyen

Filed:

06/20/2001

TI-32705

For:

Method For Annealing Ultra-Thin, High Quality Gate Oxide Layers

Using Oxidizer/Hydrogen Mixtures

## **AMENDMENT**

**Commissioner for Patents** P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Please amend the application as follows:

Cancel claims 8 and 14-16.

Respectfully submitted,

Jary C. Honeyant Garf C. Honeycutt Attorney for Applicant

972-470-0130 April 30, 2004